

## Patent Abstracts of Japan

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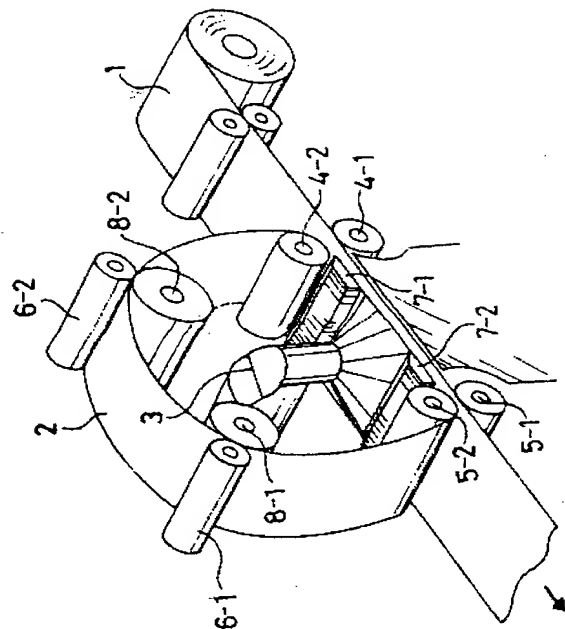
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TITLE : EXPOSING METHOD



ABSTRACT : PURPOSE: To form continuously patterns on a substrate having a long size in the moving direction with high patterning accuracy by using an endless mask as a photomask for exposure and carrying out continuous exposure while moving the photomask and the substrate at the same speed.

CONSTITUTION: A flexible substrate 1 to be exposed is coated with a photosensitive substance. The preferred material of the substrate 1 is polyimide resin or fluoro-resin. An endless flexible mask 2 has patterns of prescribed line density formed at a prescribed pitch. The substrate 1 and the mask 2 are moved at the same speed with drive rollers 4-1-6-2, and exposure is carried out with an exposer 3 during movement from a slit 7-1 to a slit 7-2. Slight reverse tension is applied to the drive rollers 4-1, 4-2 so as to prevent the slacking of the film. The exposed substrate 1 is sent to a developing device and developed at a stroke.

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